



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Rex K. Frost et al. Art Unit:
Serial No.: 10/698,782 Examiner:
Filed : October 31, 2003
Assignee : Intel Corporation
Title : ACCOMMODATING DIFFRACTION IN THE PRINTING OF
 FEATURES ON A SUBSTRATE

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information
Disclosure Statement and documents listed on form PTO-1449.

This filing is being made before the receipt of a first
Office action on the merits. No fee is required.

The documents are in the English language; hence no concise
explanation is necessary per Rule 98(a)(3).

Consideration of the foregoing and enclosures plus the
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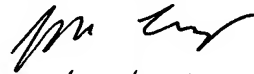
Applicant : Rex K. Frost et al.
Serial No.: 10/698,782
Filed : October 31, 2003

Attorney's Docket No.:10559-863001

Examiner's initials in the left column per MPEP 609 are
earnestly solicited along with an early action on the merits.

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Respectfully submitted,



John F. Conner, Reg # 45,485
for

Date: 2/27/04

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Substitute Form PTO-1449 (Modified) Information Disclosure Statement by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-863001	Application No. 10/698,782
	Applicant Rex K. Frost et al.		
	Filing Date October 31, 2003	Group Art Unit	

U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	6,492,069	12/2002	Wu, et al.			
	AB	6,500,587	12/2002	Ghandehari, et al.			
	AC	6,524,752	02/2003	Pierrat			
	AD	6,524,755	02/2003	Jin, et al.			
	AE	6,569,580	05/2003	Campi, et al.			
	AF						
	AG						

Foreign Patent Documents or Published Foreign Patent Applications

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
	AH							
	AI							

Other Documents (include Author, Title, Date, and Place of Publication)

Examiner Initial	Desig. ID	Document
	AJ	Liebmann, L., "Layout Impact of Resolution Enhancement Techniques: Impediment or Opportunity", <i>International Symposium on Physical Design 2003</i> , Session 7, pp. 110-117, Monterey, CA, April 6-9 (2003).
	AK	Liebmann, L., "Resolution Enhancement Techniques in Optical Lithography, It's not just a Mask Problem", <i>Proceedings SPIE, Photomask and Next-Generation Lithography Mask Technology VIII</i> , Vol. 4409, pp. 23-32 (2001).
	AL	Nordquist, K., et al., "Critical Dimension and Image Placement Issues for Step and Flash Imprint Lithography Templates", <i>Proceedings of SPIE, 22nd Annual BACUS Symposium on Photomask Technology</i> , Vol. 4889, No. 129, pp. 1143-1150 (2002).
	AM	Petersen, J., et al., "Development of a Sub-100nm Integrated Imaging System Using Chromeless Phase-Shifting Imaging with Very High NA KrF Exposure and Off-axis Illumination", <i>Proceedings SPIE, Design, Process Integration, and Characterization for Microelectronics</i> , Vol. 4692, pp. 298-311 (2002).
	AN	Scheid, G., et al., "Contact Holes: Optical Area Measurement Predicts Printability and is Highly Repeatable", presented at Photomask Japan 2001, Paper 4409-11, pp. 1-6 (2001).
	AO	Zhang, H., et al., "Compact Formulation of Mask Error Factor for Critical Dimension Control in Optical Lithography", <i>Proceedings SPIE, Metrology, Inspection, and Process Control for Microlithography XVI</i> , Vol. 4689, pp. 462-465 (2002).
	AP	

Examiner Signature	Date Considered
EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	